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Cont

magnesium oxide in a molar ratio with the basic material of 3% to 45% magnesium oxide, yttrium oxide in a molar ratio with the basic material of 10% to 80% yttrium oxide, gallium nitride in a molar ratio with the basic material of 1% to 30% gallium nitride, silicon nitride in a molar ratio with the basic material of 10% to 85% silicon nitride, aluminum nitride in a molar ratio with the basic material of 1% to 50% aluminum nitride, silicon carbide in a molar ratio with the basic material of 5% to 50% silicon carbide, and titanium carbide in a molar ratio with the basic material of 10% to 85% titanium carbide

## **REMARKS**

Claim 16 has been added, and the species of claim 11-13 have been elected.

The Office is hereby authorized to charge any additional fees which may be required in connection with this amendment and to credit any overpayments to our Deposit Account No. 03-3125.

If a telephone interview could advance the prosecution of this application, the Examiner is respectfully requested to call the undersigned attorney.

The entry of this amendment and the allowance of this application are respectfully requested.

Respectfully submitted,

RICHARD F. JAWORSKI Registration No. 33,515 Attorney for Applicant

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## **VERSION WITH MARKINGS TO SHOW CHANGES IN CLAIMS**

16. (New) A protection layer for a data recording medium, the protection layer comprising:

a basic material; and

a compound having a thermal conductivity greater than or equal to 10 W/m.deg when in a bulk state, said compound comprising one or more of the compounds selected from the group consisting of:

titanium oxide in a molar ratio with the basic material of 3% to 50% zinc oxide, titanium oxide in a molar ratio with the basic material of 10% to 98% titanium oxide, magnesium oxide in a molar ratio with the basic material of 3% to 45% magnesium oxide, yttrium oxide in a molar ratio with the basic material of 10% to 80% yttrium oxide, gallium nitride in a molar ratio with the basic material of 1% to 30% gallium nitride, silicon nitride in a molar ratio with the basic material of 1% to 50% aluminum nitride, silicon carbide in a molar ratio with the basic material of 1% to 50% aluminum nitride, silicon carbide in a molar ratio with the basic material of 5% to 50% silicon carbide, and titanium carbide in a molar ratio with the basic material of 10% to 85% titanium carbide.